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				Application Number	10/780,667
				Filing Date	February 19, 2004
				First Named Inventor	Hironori Ibusuki
				Art Unit	1756
				Examiner Name	C. G. Young
Sheet	1	of	1	Attorney Docket Number	SON-2920

U.S. PATENT DOCUMENTS					
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FOREIGN PATENT DOCUMENTS					
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NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			
/CY/	CA	EPL: Electron-beam Proximity Lithography, "Projection Exposure with Variable Axis Immersion Lenses: A High-Throughput Electron Beam Approach to Suboptical Lithography" H.C Pfeiffer, Jpn. J. Appl. Phys. Vol. 34 (1995) pp. 6658-6662			
/CY/	CB	LEEPL: Low Energy Electron-beam Proximity Projection Lithography, "Characterization of a Process Development Tool for Ion Projection Lithography, Hans Loeschner, et al, J.Vac. Sci. technol. B19, (2001)			
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Examiner Signature	/Christopher Young/ (06/08/2007)	Date Considered	06/08/2007
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